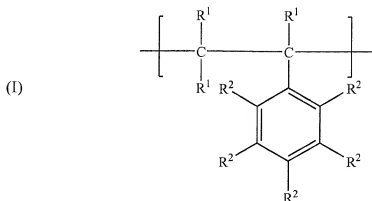
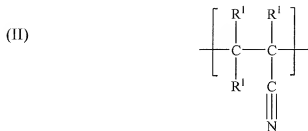


Claims:

1. (Withdrawn) A microelectronic structure comprising:
 a microelectronic substrate surface; and
 a first protective layer adjacent said substrate surface, said first protective layer including a polymer comprising recurring monomers having the respective formulas



and



wherein:

each R¹ is individually selected from the group consisting of hydrogen and

C₁-C₈ alkyls; and

each R² is individually selected from the group consisting of hydrogen, C₁-C₈

alkyls, and C₁-C₈ alkoxys,

said layer being essentially nonconductive.

2. (Withdrawn) The structure of claim 1, wherein said polymer comprises at least about 50% by weight of monomer I, based upon the total weight of the polymer taken as 100% by weight.

3. (Withdrawn) The structure of claim 1, wherein said polymer comprises at least about 15% by weight of monomer (II), based upon the total weight of the polymer taken as 100% by weight.

4. (Withdrawn) The structure of claim 1, said first protective layer having an average thickness of from about 1-5 μm .

5. (Withdrawn) The structure of claim 1, said structure further comprising a primer layer intermediate said substrate and said first protective layer.

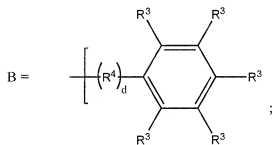
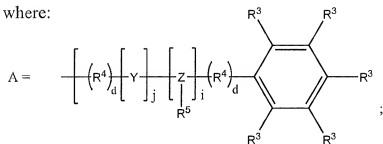
6. (Withdrawn) The structure of claim 5, said primer layer having an average thickness of less than about 10 nm.

7. (Withdrawn) The structure of claim 5, said primer layer comprising a silane.

8. (Withdrawn) The structure of claim 7, said silane having the structure



where:



each of i, j, and k is individually selected from the group consisting of 0 and 1, and if one of i and j is 1, then the other of i and j is 0;

each R³ is individually selected from the group consisting of hydrogen, the halogens, C₁-C₈

alkyls, C₁-C₈ alkoxys, C₁-C₈ haloalkyls, aminos, and C₁-C₈ alkylaminos;

each R⁴ is individually selected from the group consisting of C₁-C₈ aliphatic groups;

each X is individually selected from the group consisting of halogens, hydroxyls, C₁-C₄

alkoxys and C₁-C₄ carboxyls;

Y is selected from the group consisting of oxygen and sulfur;

Z is selected from the group consisting of nitrogen and phosphorus; and

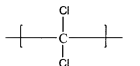
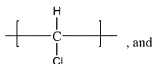
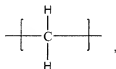
each d is individually selected from the group consisting of 0 and 1.

9. (Withdrawn) The structure of claim 1, said structure further comprising a second protective layer adjacent said first protective layer.

10. (Withdrawn) The structure of claim 9, said second protective layer comprising a halogenated polymer.

11. (Withdrawn) The structure of claim 10, said halogenated polymer comprising at least about 50% by weight halogen atoms, based upon the total weight of the halogenated polymer taken as 100% by weight.

12. (Withdrawn) The structure of claim 10, wherein said halogenated polymer is a chlorinated polymer comprising recurring monomers having the formula



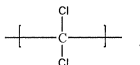
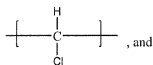
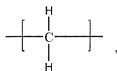
13. (Withdrawn) The structure of claim 10, wherein said halogenated polymer is a chlorinated polymer selected from the group consisting of poly(vinyl chloride), polyvinylidene chloride, poly(vinylidene dichloride)-co-poly(vinyl chloride), chlorinated ethylene, chlorinated propylene, chlorinated rubbers, and mixtures thereof.

14. (Withdrawn) The structure of claim 5, said structure further comprising a second protective layer adjacent said first protective layer.

15. (Withdrawn) The structure of claim 14, said second protective layer comprising a halogenated polymer.

16. (Withdrawn) The structure of claim 15, said halogenated polymer comprising at least about 50% by weight halogen atoms, based upon the total weight of the halogenated polymer taken as 100% by weight.

17. (Withdrawn) The structure of claim 15, wherein said halogenated polymer is a chlorinated polymer comprising recurring monomers having the formula



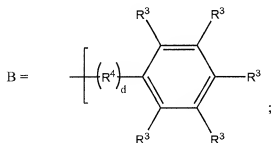
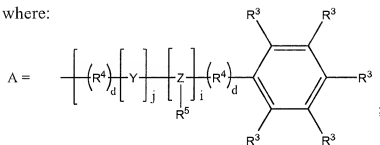
18. (Withdrawn) The structure of claim 15, wherein said halogenated polymer is a chlorinated polymer selected from the group consisting of poly(vinyl chloride), polyvinylidene chloride, poly(vinylidene dichloride)-co-poly(vinyl chloride), chlorinated ethylene, chlorinated propylene, chlorinated rubbers, and mixtures thereof.

19. (Withdrawn) The structure of claim 14, said primer layer comprising a silane.

20. (Withdrawn) The structure of claim 19, said silane comprising the structure



where:



each of i, j, and k is individually selected from the group consisting of 0 and 1, and if one of

i and j is 1, then the other of i and j is 0;

each R³ is individually selected from the group consisting of hydrogen, the halogens, C₁-C₈

alkyls, C₁-C₈ alkoxys, C₁-C₈ haloalkyls, aminos, and C₁-C₈ alkylaminos;

each R⁴ is individually selected from the group consisting of C₁-C₈ aliphatic groups;

each X is individually selected from the group consisting of halogens, hydroxyls, C₁-C₄ alkoxys and C₁-C₄ carboxyls;

Y is selected from the group consisting of oxygen and sulfur;

Z is selected from the group consisting of nitrogen and phosphorus; and

each d is individually selected from the group consisting of 0 and 1.

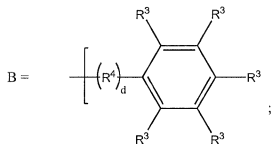
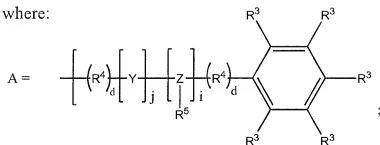
21. (Withdrawn) The structure of claim 14, wherein said primer layer comprises an aromatic silane, and said second protective layer comprises a halogenated polymer.

22. (Withdrawn) The structure of claim 1, wherein said microelectronic substrate is selected from the group consisting of Si substrates, SiO₂ substrates, Si₃N₄ substrates, SiO₂ on silicon substrates, Si₃N₄ on silicon substrates, glass substrates, quartz substrates, ceramic substrates, semiconductor substrates, and metal substrates.

23. (Currently Amended) A microelectronic structure comprising:
 a microelectronic substrate having a surface;
 a primer layer adjacent said substrate surface, said primer layer comprising a silane having
 the structure



where:



each of i, j, and k is individually selected from the group consisting of 0 and 1, and
 if one of i and j is 1, then the other of i and j is 0;

each R³ is individually selected from the group consisting of hydrogen, the halogens,

C₁-C₈ alkyls, C₁-C₈ alkoxys, C₁-C₈ haloalkyls, aminos, and C₁-C₈ alkylaminos;

each R⁴ is individually selected from the group consisting of C₁-C₈ aliphatic groups;

each X is individually selected from the group consisting of halogens, hydroxyls, C₁-C₄ alkoxys and C₁-C₄ carboxyls;

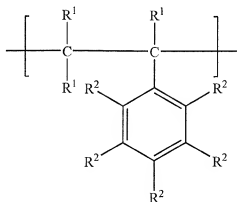
Y is selected from the group consisting of oxygen and sulfur;

Z is selected from the group consisting of nitrogen and phosphorus; and

each d is individually selected from the group consisting of 0 and 1; and

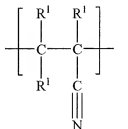
a first protective layer adjacent said primer layer, said first protective layer including a polymer comprising recurring monomers having the respective formulas

(I)



and

(II)



wherein:

each R¹ is individually selected from the group consisting of hydrogen and C₁-C₈ alkyls; and

each R² is individually selected from the group consisting of hydrogen, C₁-C₈ alkyls, and C₁-C₈ alkoxys; and

a second protective layer adjacent said first protective layer, said second protective layer comprising a halogenated polymer.

24. (Original) The structure of claim 23, wherein said polymer comprises at least about 50% by weight of monomer I, based upon the total weight of the polymer taken as 100% by weight.

25. (Original) The structure of claim 23, wherein said polymer comprises at least about 15% by weight of monomer (II), based upon the total weight of the polymer taken as 100% by weight.

26. (Original) The structure of claim 23, said first protective layer having an average thickness of from about 1-5 μm .

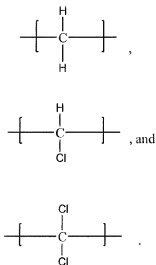
27. (Canceled)

28. (Original) The structure of claim 23, said primer layer having an average thickness of less than about 10 nm.

29.-31. (Canceled)

32. (Currently Amended) The structure of claim ~~31~~23, said halogenated polymer comprising at least about 50% by weight halogen atoms, based upon the total weight of the halogenated polymer taken as 100% by weight.

33. (Currently Amended) The structure of claim ~~34~~23, wherein said halogenated polymer is a chlorinated polymer comprising recurring monomers having the formula



34. (Currently Amended) The structure of claim ~~34~~23, wherein said halogenated polymer is a chlorinated polymer selected from the group consisting of poly(vinyl chloride), polyvinylidene chloride, poly(vinylidene dichloride)-co-poly(vinyl chloride), chlorinated ethylene, chlorinated propylene, chlorinated rubbers, and mixtures thereof.

35. (Original) The structure of claim 23, wherein said microelectronic substrate is selected from the group consisting of Si substrates, SiO₂ substrates, Si₃N₄ substrates, SiO₂ on silicon substrates, Si₃N₄ on silicon substrates, glass substrates, quartz substrates, ceramic substrates, semiconductor substrates, and metal substrates.

36-68. (Canceled)

69. (Withdrawn) A microelectronic structure comprising:

a microelectronic substrate having a surface;

a primer layer adjacent said substrate surface;

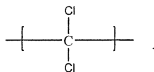
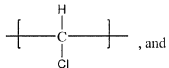
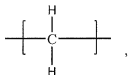
a first protective layer adjacent said primer layer, said first protective layer comprising a polymer dispersed or dissolved in a solvent system; and

a second protective layer adjacent said first protective layer, said second protective layer comprising a halogenated polymer dispersed or dissolved in a solvent system.

70. (Withdrawn) The structure of claim 69, wherein said halogenated polymer comprises a chlorinated polymer.

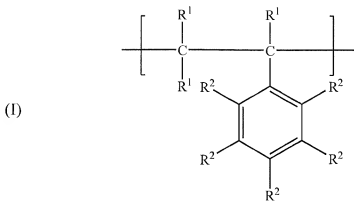
71. (Withdrawn) The structure of claim 70, wherein said chlorinated polymer comprises at least about 50% by weight chlorine atoms, based upon the total weight of the chlorinated polymer taken as 100% by weight.

72. (Withdrawn) The structure of claim 70, wherein said halogenated polymer is a chlorinated polymer comprising recurring monomers having the formula

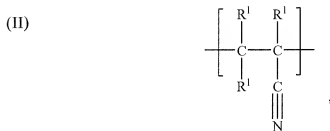


73. (Withdrawn) The structure of claim 70, wherein said halogenated polymer is selected from the group consisting of poly(vinyl chloride), polyvinylidenechloride, poly(vinylidene dichloride)-co-poly(vinyl chloride), chlorinated ethylene, chlorinated propylene, chlorinated rubbers, and mixtures thereof.

74. (Withdrawn) The structure of claim 69, wherein said first protective layer comprises a polymer comprising recurring monomers having the respective formulas



and



wherein:

each R¹ is individually selected from the group consisting of hydrogen and

C₁-C₈ alkyls; and

each R² is individually selected from the group consisting of hydrogen, C₁-C₈

alkyls, and C₁-C₈ alkoxys.

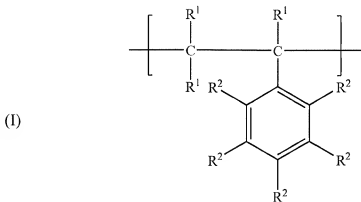
75-77. (Canceled)

78. (Currently Amended) A microelectronic structure comprising:

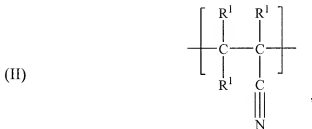
a microelectronic substrate having a surface, said microelectronic substrate being selected from the group consisting of Si substrates, SiO₂ substrates, Si₃N₄ substrates, SiO₂ on silicon substrates, Si₃N₄ on silicon substrates, quartz substrates, ceramic substrates, and semiconductor substrates;

a primer layer adjacent said substrate surface; and

a first protective layer adjacent said primer layer, said first protective layer including a polymer comprising recurring monomers having the respective formulas



and



wherein:

each R¹ is individually selected from the group consisting of hydrogen and

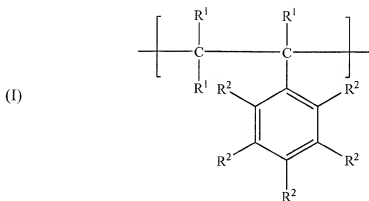
C₁-C₈ alkyls; and

each R² is individually selected from the group consisting of hydrogen, C₁-C₈

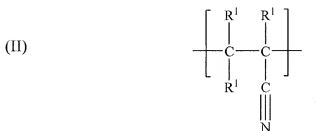
alkyls, and C₁-C₈ alkoxy; and

a second protective layer adjacent said first protective layer, said second protective layer comprising a halogenated polymer.

79. (Currently Amended) A microelectronic structure comprising:
 a microelectronic substrate having a surface;
 a primer layer adjacent said substrate surface; and
 a first protective layer adjacent said primer layer, said first protective layer including a polymer comprising recurring monomers having the respective formulas



and



wherein:

each R¹ is individually selected from the group consisting of hydrogen and C₁-C₈ alkyls; and

each R² is individually selected from the group consisting of hydrogen, C₁-C₈ alkyls, and C₁-C₈ alkoxys

wherein said polymer comprises from about 20-35% by weight of structure (II),

based upon the total weight of the polymer taken as 100% by weight; and
a second protective layer adjacent said first protective layer, said second protective layer
comprising a halogenated polymer.

80. (New) The structure of claim 23, said second protective layer having an average thickness of from about 1-5 μm .

81. (New) The structure of claim 78, said first protective layering having an average thickness of from about 1-5 μm .

82. (New) The structure of claim 78, said second protective layer having an average thickness of from about 1-5 μm .

83. (New) The structure of claim 79, said first protective layering having an average thickness of from about 1-5 μm .

84. (New) The structure of claim 79, said second protective layer having an average thickness of from about 1-5 μm .